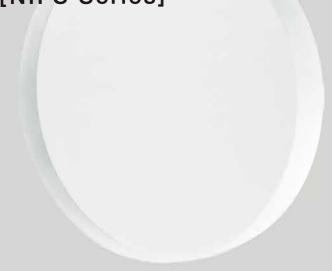


OPTICAI NIAIRIAIS

Synthetic Silica Glass

[NIFS Series]



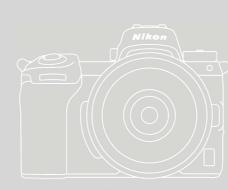
Nikon optics are used in various fields.

Nikon optics are not limited to our own cameras and lithography systems. It is also used in various fields such as 3D Printers, Optical Systems, Interferometers, Laser Processing Machines, and so on.

Silica glass stands out among optical materials that offer various properties and capabilities. It provides the highest standards of purity, homogeneity, and laser durability. Nikon Synthetic Silica Glass (SiO₂), NIFS series, features high refractive index homogeneity, high transmittance, and superior excimer laser durability. Nikon has the capability of factoring in any material-grade specification, or mass-production quality using its proprietary accurate-analysis technology and material measurement to meet our customer requirements and exceed expectations.

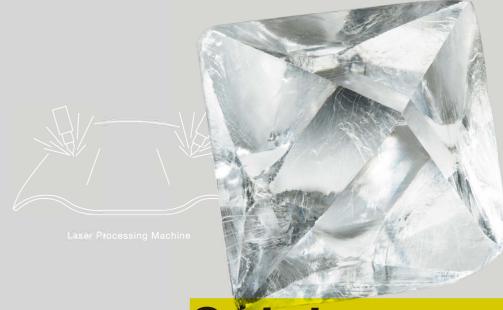






Camora





Calcium Fluoride [NICF Series]

accurate-analysis and measurement.

Nikon Calcium Fluoride, NICF Series, are single-crystal optical material that features high homogeneity in its refractive index, high transmittance, and high durability from Excimer Laser to Vacuum Ultraviolet Lasers. Nikon Calcium Fluoride was originally developed to accommodate optics for Illumination System and/or Projection Lens System on our Semiconductor Lithography System. While working with

calcium fluoride to match our customer requirements, Nikon has the capability of factoring in any material-grade specification and mass-production criterion using proprietary



3D Printer

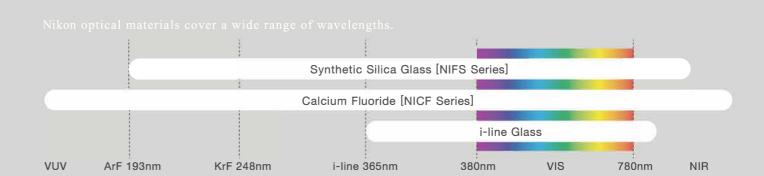




Optical System



Together with Nikon Optical Design, we have been Researching and Developing high-quality optics and optical products. Nikon i-line Glass was developed to be used in our i-line (365 nm) semiconductor lithography systems. It delivers high transmittance and superior homogeneity, even with large diameter optics.





Calcium Fluoride

[NICF Series]





Applications

Ultraviolet and High-Power Laser Optics

Industrial Inspection System Lenses and Optics
Synthetic Silica Glass Wafers
Various Device Substrates (e.g. TFT, CCD, etc.)
Astronomy Optics
Healthcare, Medical System Optics
Semiconductor Manufacturing Equipment Optics
Semiconductors/FPD Synthetic Silica Photomask Substrates

Semiconductor and FPD Lithography System Lenses and Optics

Lineup

Grade	Internal Transmittance [%] Sample thickness: 10 mm	Birefringence	Striae	Recommended Wavelength	
NIFS-V	99.9 (at 193 nm)		3D	ArF (193 nm)	
NIFS-A	99.9 (at 193 nm)	99.9 (at 193 nm)	3D 1D	ArF (193 nm)	
NIFS-U	99.9 (at 248 nm) 1~10 nm/cm	3D 1D	KrF (248 nm)		
NIFS-S	99.9 (at 365 nm)		3D 1D	UV region, Visible region	
NIFS-I	-		-	-	

Striae free in three directions (all directions) or Striae free in one direction can be selected along with its Striae grade.



Applications

Ultraviolet and High-Power Laser Optics Semiconductor and FPD Lithography System Lenses and Optics Industrial Inspection System Lenses and Optics Camera Lenses Astronomic Optics

Lineup

Grade	Internal Transmittance [%] Sample thickness: 10 mm	Birefringence	Recommended Wavelength
NICF-V	≧99 . 5 (at 157 nm)		VUV region, ArF (193 nm)
NICF-A	≧99.8 (at 193 nm)	2~20 nm/cm on request	ArF (193 nm)
NICF-U	≧99.8 (at 248 nm)	on request	KrF (248 nm)
NICF-S	-		UV region, Visible region, IR region

Crystal Orientation and Various Properties are selectable.

i-line Glass





Applications

Semiconductor and FPD Lithography System Lenses and Optics Industrial Inspection System Lenses and Optics Various Inspection/Measurement System Lenses and Optics

Lineup

Glass type	Refractive index	Dispersion V _d	10 mm internal transmittance [%] (365 nm)τ _i	Refractive index n _i	Single lot variation n _i (×10 ⁻⁵)	Solarization
4786	1.47410	86.8	99.8	1.48726	2	Good
5165	1.51183	65.0	99.8	1.53073	10	Good
5742	1.57653	42.1	99.6	1.61265	2	Good
5859	1.59042	59.5	99.7	1.61450	2	Good
7054	1.70623	54.7	99.4	1.73811	10	Good

¹⁰ mm Internal Transmittance:

Representative value of the light transmittance at i-line (365 nm) with glass of 10 mm thickness, excluding reflection losses. Refractive index:

Representative value of the refractive index at i-line (365 nm). Depending on the required quality, longer annealing time would be required and the refractive index value would change. The data presented are based on Nikon standard annealing condition.

Refractive index variation of a part within a single lot, with the same melt and same annealing condition.





1. Optical Design



2. Optical Materials
Synthetic Silica, Calcium Fluori



3. Processing
Grinding, Polishing, Coatin



4. Optical Modules

Projection Lens,
Objective Lens, etc.

